

**IN THE CLAIMS:**

Claim 1 (currently amended): A method of fabricating a liquid crystal display device, comprising the steps of:

forming a first metal layer on a substrate to form a gate line including a gate electrode, a gate pad, and a first capacitor electrode;

forming an insulating layer, an active layer, and a second metal layer on the substrate;

patterning the second metal layer to form a data line including a data pad, a source electrode, a drain electrode, and a second capacitor electrode;

forming a passivation layer to cover the second metal layer;

forming a photoresist on the passivation layer;

exposing the photoresist using a mask having a plurality of light shielding ~~{portion}~~ portions, a plurality of light transmissive ~~{portion}~~ portions, and a plurality of semi-transmissive ~~{portion}~~ portions;

forming a plurality of first photoresist ~~{portion}~~ portions, a plurality of second photoresist ~~{portion}~~ portions, and a plurality of third photoresist ~~{portion}~~ portions;

patterning the passivation layer, the active layer, and the insulating layer; and

forming a pixel electrode on the passivation layer,

wherein each of the plurality of semi-transmissive portions correspond to at least one of the gate pad, the source electrode, and the drain electrode.

Claim 2 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the gate line and the data line cross with each other to define a pixel region, and the source electrode and the drain electrode are spaced apart from each other.

Claim 3 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the step of depositing and patterning a first metal layer includes a first masking step.

Claim 4 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the step of depositing an insulating layer, an active layer, and a second metal layer includes a second masking step.

Claim 5 (original): The method of fabricating a liquid crystal display device according to Claim 4, wherein the step of patterning the second metal layer is included in the second masking step.

Claim 6 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the steps of forming a passivation layer, forming a photoresist, exposing the photoresist, forming first, second and third photoresist portions, and patterning the passivation layer are included in a third masking step.

Claim 7 (original): The method of fabricating a liquid crystal display device according to Claim 6, wherein, in the third masking step, a side portion and upper surfaces of the drain electrode are uncovered, a capacitor contact hole is formed over the second capacitor electrode, and a data pad contact hole is formed over the data pad through the passivation layer, and a gate pad contact hole is formed over the gate pad passing through the insulating layer, the active layer, and the passivation layer.

Claim 8 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein each of the third photoresist ~~[portion has]~~ portions have a thickness of 800 to 900 Å.

Claim 9 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the first metal layer includes at least a first aluminum neodymium (AlNd) material layer and a second molybdenum (Mo) material layer.

Claim 10 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the insulating layer and the passivation layer include at least an inorganic insulating material.

Claim 11 (original): The method of fabricating a liquid crystal display device according to Claim 10, wherein the inorganic insulating material includes at least one material selected from a group consisting of silicon oxide ( $\text{SiO}_2$ ) and silicon nitride ( $\text{SiN}_x$ ).

Claim 12 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the insulating layer and the passivation layer include at least organic insulating materials.

Claim 13 (original): The method of fabricating a liquid crystal display device according to Claim 12, wherein the organic insulating materials include at least one material selected from a group consisting benzocyclobutene (BCB) and an acryl-based resin.

Claim 14 (original) The method of fabricating a liquid crystal display device according to Claim 1, wherein a portion of the passivation layer disposed over the data line has a width smaller than a corresponding width of the data line.

Claim 15 (currently amended): The method of fabricating a liquid crystal display device according to Claim 1, wherein the light shielding ~~{portion}~~ portions of the mask ~~{includes}~~ include at least an opaque metal material having a low reflectivity.

Claim 16 (original): The method of fabricating a liquid crystal display device according to Claim 15, wherein the opaque metal includes at least a chromium (Cr) material.

Claim 17 (original): The method of fabricating a liquid crystal display device according to Claim 1, wherein the semi-transmissive portion of the mask includes at least a molybdenum silicide (MoSi) material.

Claims 18-28 (canceled).